

Lithographic Device, Device Manufacturing Method and Device Manufactured Thereby

ABSTRACT:

5 A lithographic projection apparatus comprising:

- a radiation system for supplying a projection beam of radiation;
 - a mask table provided with a mask holder for holding a mask;
 - a substrate table provided with a substrate holder for holding a substrate;
 - a projection system for imaging an irradiated portion of the mask onto a target portion of
- 10 the substrate,

whereby:

a) the projection system is separated from the substrate table by an intervening space which can be at least partially evacuated and which is delimited at the location of the projection system by a solid surface from which the employed radiation is directed toward the

15 substrate table;

b) the intervening space contains a hollow tube located between the solid surface and the substrate table and situated around the path of the radiation, the form and size of the tube being such that radiation focused by the projection system onto the substrate table does not intercept a wall of the hollow tube;

20 c) means are provided for continually flushing the inside of the hollow tube with a flow of gas, wherein the gas is hydrogen, helium, deuterated hydrogen, deuterium or a mixture of argon and hydrogen and the flow of the gas is opposed to the flow of contaminants from the substrate and/or the hollow tube is in fluidic communication with the intervening space.

25 Figure 3